



United States Patent and Trademark Office

UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMISSIONER OF PATENTS AND TRADEMARKS Washington, D.C. 20231 www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/648,657	08/25/2000	Yoshimasa Chikama	55058(820)	5508
21874	7590 03/31/2003			
EDWARDS & ANGELL, LLP			EXAMINER	
P.O. BOX 916 BOSTON, MA		,	ALANKO, ANITA KAREN	
			ART UNIT	PAPER NUMBER
			1765	
			DATE MAILED: 03/31/2003	3

Please find below and/or attached an Office communication concerning this application or proceeding.

		m/c -12				
•	Application No.	Applicant(s)				
Office Action Summary	09/648,657	CHIKAMA ET AL.				
Office Action Summary	Examiner	Art Unit				
The MAILING DATE of this communication app	Anita K Alanko	1765				
Period for Reply	ears on the cover sheet whit the c	orrespondence address				
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply - If NO period for reply is specified above, the maximum statutory period w - Failure to reply within the set or extended period for reply will, by statute, - Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b). Status	36(a). In no event, however, may a reply be time within the statutory minimum of thirty (30) day will apply and will expire SIX (6) MONTHS from cause the application to become ABANDONE	nely filed s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).				
1) Responsive to communication(s) filed on	·					
2a)⊠ This action is FINAL . 2b)□ Th	is action is non-final.					
3) Since this application is in condition for allows						
closed in accordance with the practice under Disposition of Claims	Ex parte Quayle, 1935 C.D. 11, 4	.53 O.G. 213.				
4) Claim(s) <u>1,2,4-9 and 11-15</u> is/are pending in the	he application.					
4a) Of the above claim(s) is/are withdrawn from consideration.						
5) Claim(s) is/are allowed.						
6)⊠ Claim(s) <u>1,2,4-9 and 11-15</u> is/are rejected.						
7) Claim(s) is/are objected to.						
8) Claim(s) are subject to restriction and/o	r election requirement.					
Application Papers						
9) The specification is objected to by the Examine		minor				
10) The drawing(s) filed on is/are: a) accept						
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a). 11) The proposed drawing correction filed on is: a) approved b) disapproved by the Examiner.						
If approved, corrected drawings are required in reply to this Office action.						
12) The oath or declaration is objected to by the Examiner.						
Priority under 35 U.S.C. §§ 119 and 120						
13) Acknowledgment is made of a claim for foreign	n priority under 35 LLS C. & 119/a)-(d) or (f)				
a) All b) Some * c) None of:	i priority under do o.o.o. 3 1 10(c	, (d) 31 (i).				
1. Certified copies of the priority document	s have been received.					
Certified copies of the priority documents have been received in Application No						
Copies of the certified copies of the prior application from the International Bu * See the attached detailed Office action for a list	rity documents have been receive reau (PCT Rule 17.2(a)).	ed in this National Stage				
14) Acknowledgment is made of a claim for domesti	·					
a) ☐ The translation of the foreign language pro	visional application has been rec	eived.				
Attachment(s)						
1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449) Paper No(s) 8	5) Notice of Informal I	r (PTO-413) Paper No(s) Patent Application (PTO-152)				
S. Patent and Trademark Office						

Paper No. 12 Art Unit: 1765

Information Disclosure Statement

The information disclosure statement filed 8/13/02 has been considered. The Korean document has been considered to the extent that it is disclosed in US 5,300,813.

The search report and Korean office action are missing from the IDS submission. The search report does not appear to be attached to amendment "a" filed Feb.10, 2003.

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 1-2, 4, 6-7, 9 and 11 are rejected under 35 U.S.C. 102(b) as being clearly anticipated by Takada et al (US 4,629,681).

Takada discloses a method comprising (col.3, lines 6-38, col.4, lines 1-3):

forming a ground resin film why applying a resin onto an insulating substrate 1 (a ceramic);

patterning the ground resin film (Fig.3, to form through-holes);

forming a low-resistance metal film 8 selectively on and over the patterned group resin film by a wet film formation technique, wherein the low-resistance metal film is a single layer film containing Cu or Ni, or a multilayer film containing Cu or Ni (Fig.4).

Alalo3

Paper No. 12 Art Unit: 1765

Claims 1-2, 4-9 and 11-13 are rejected under 35 U.S.C. 102(b) as being clearly anticipated by O'Sullivan et al (US 5,310,580).

O'Sullivan discloses a method comprising (col.4, lines 22-50; col.5, lines 48-49):

forming a ground resin film 10 by applying a resin onto an insulating substrate 12 (silicon, glass or ceramic);

patterning the ground resin film (Fig. 1a shows that the film is selectively patterned);

forming a low-resistance metal film 20 selectively on and over the patterned group resin film by a wet film formation technique, wherein the low-resistance metal film is a single layer film containing Cu or Ni, or a multilayer film containing Cu or Ni (Fig. 1c; col.6, lines 36+).

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1-2,4, 6-9, 11-14 are rejected under 35 U.S.C. 103(a) as being unpatentable over Takada et al (US 4,629,681) in view of JP 10-245,444 and Larsson et al (U.S. Patent No. 6,303,278 B1).

The discussion of Takada from above is repeated here.

As to claims 8, 12 and 14 Takada does not teach to reduce metal ions by irradiating ultraviolet rays and KOH treatment.

Paper No. 12 Art Unit: 1765

JP 10-245,444 teaches a useful method for forming a metal film on polyimide with excellent adhesion force (paragraph [0004]), including: forming a polyimide resin film, followed by modifying the surface with KOH, reducing metal ions and plating (see Example, paragraphs [0016]-[0018] of translation).

It would have been obvious to one with ordinary skill in the art to form the metal on the polyimide film in the method of Takada using the method of JP 10-245,444 of modifying the polyimide surface and then plating because JP 10-245,444 teaches that it is useful for forming a film with excellent adhesion force.

Further, as to claim 14, JP 10-245,444 discloses to use a solution to reduce the nickel metal ions to nickel. Larsson teaches that an equivalent alternative technique for using a solution for the reduction is a photochemical technique (col.5, lines 34-41). Larsson teaches that ultraviolet light is useful for the reduction process (col.7, line 35). It would have been obvious to use ultraviolet light to reduce the metal ions to metal in the method of Takada modified by JP 10-245,444 because Larsson teaches that this is a useful, functionally equivalent technique compared to solution processing.

Claims 1-2, 4-7, 9 and 11 are rejected under 35 U.S.C. 103(a) as being unpatentable over Takada et al (US 4,629,681) in view of Iwasaki et al (U.S. Patent No. 5,323,534).

The discussion of Takada from above is repeated here.

As to claim 5, Takada does not teach add catalyst to the resin. Iwasaki teaches that adding a catalyst to resins is conventional in order to prepare for subsequent plating (col.11, lines 63-65). It would have been obvious to one with ordinary skill in the art to add the catalyst to the

Paper No. 12 Art Unit: 1765

resin in the method of Takada in order to save time and money and decrease contamination by not requiring multiple steps for forming catalyst films, and because it is a conventional technique in plating as taught by Iwasaki.

Claims 1-2, 4, 6-7, 9, 11 and 15 are rejected under 35 U.S.C. 103(a) as being unpatentable over Takada et al (US 4,629,681) in view of Kishomoto et al (U.S. Patent No. 5,516,983).

The discussion of Takada from above is repeated here.

As to claim 15, Takada does not disclose the thickness of the polyimide layer. The method of Takada is directed to making a multilayer circuit board. Kishimoto teaches that polyimide layers of 0.3 microns, which is within the cited range, are useful thicknesses for electronic devices (col.6, example 3). It would have been obvious to one with ordinary skill in the art to form the polyimide layer in the method of Takada to the cited thickness because Kishimoto teaches that thicknesses on the same order of magnitude are useful for forming electronic devices.

Response to Amendment

The 35 U.S.C. 112, second paragraph rejection is withdrawn.

The rejections over Joshi are withdrawn.

Claims 1-2, 4, 6-7, 9 and 11 are rejected under 35 U.S.C. 102(b) as being clearly anticipated by Takada et al (US 4,629,681).

Paper No. 12 Art Unit: 1765

Claims 1-2, 4-9 and 11-13 are rejected under 35 U.S.C. 102(b) as being clearly anticipated by O'Sullivan et al (US 5,310,580).

Claims 1-2,4, 6-9, 11-14 are rejected under 35 U.S.C. 103(a) as being unpatentable over Takada et al (US 4,629,681) in view of JP 10-245,444 and Larsson et al (U.S. Patent No. 6,303,278 B1).

Claims 1-2, 4-7, 9 and 11 are rejected under 35 U.S.C. 103(a) as being unpatentable over Takada et al (US 4,629,681) in view of Iwasaki et al (U.S. Patent No. 5,323,534).

Claims 1-2, 4, 6-7, 9, 11 and 15 are rejected under 35 U.S.C. 103(a) as being unpatentable over Takada et al (US 4,629,681) in view of Kishomoto et al (U.S. Patent No. 5,516,983).

Response to Arguments

Applicant's arguments filed 8/13/02 have been fully considered. Examiner acknowledges that Joshi does not disclose the new limitation in claim 1 of forming a low-resistance metal film over the patterned ground resin film. The new references applied show metal film formed over the polyimide layer.

Conclusion

Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

Paper No. 12 Art Unit: 1765

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Anita K Alanko whose telephone number is 703-305-7708. The examiner can normally be reached on Monday-Friday, 10:00 am-4:00 pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Benjamin Utech can be reached on 703-308-3836. The fax phone numbers for the organization where this application or proceeding is assigned are 703-872-9057 for regular communications and 703-872-9311 for After Final communications.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-0661.

Anita K. Hanko

Primary Examiner
Art Unit 1765

Paper No. 12 Art Unit: 1765

AKA

March 21, 2003

Page 8